

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[MA2] Nanoscale Thin Film Deposition II
Session Date:	November 14 (Mon.), 2022
Session Time:	15:00-16:45
Session Room:	Room A (Capri Room, 2F)
Session Chair:	Prof. Hyeongtag Jeon (Hanyang Univ., Korea)

[MA2-1] [Plenary] 15:00-15:45

Controlling Atomic Layer Deposition for Advanced Semiconductor Manufacturing
Stacey F. Bent (Stanford Univ., USA)

[MA2-2] 15:45-16:05

Seam-less Deposition of TiO₂ Using Gradient Selective Deposition
Chi Thang Nguyen and Han-Bo-Ram Lee (Incheon Nat'l Univ., Korea)

[MA2-3] 16:05-16:25

Analysis on an Alternative Pathway for Low-Temperature Atomic Layer Deposition of Nitrides
Jinwoo Lee, Soo Hyun Lee, Tran Thi Ngoc Van, and Bonggeun Shong (Hongik Univ., Korea)

[MA2-4] 16:25-16:45

There Is More Room for Plasma in PE-CVD/ALD
Hyungjoo Shin (Wonik IPS Co., Ltd., Korea)